

ABSTRACT OF THE DISCLOSURE

The present invention relates to an overlay mark used for the measurement of the overlay accuracy between layered patterns and alignment at the time of exposure;

5 which has a grooved pattern surrounding a mark pattern that is formed by engraving a groove or an indent in a prescribed position on a layer where a circuit pattern is formed so as to protect this mark pattern from being deformed by thermal expansion or contraction of this

10 layer. The present invention enables to form a multi-layered circuit pattern with a high accuracy and a high yield in production, even in the formation of a minute and densely-spaced circuit pattern.